

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Richard H. Lane

Group Art Unit: 2892

Application No.: 09/989,372

Examiner: Chuong A. Luu

Filed: November 21, 2001

Confirmation No.: 1348

For: ELECTROPOLISHED PATTERNED METAL
LAYER FOR SEMICONDUCTOR DEVICES

Allowed: July 24, 2009

**COMMENTS ON EXAMINER'S
STATEMENT OF REASONS FOR ALLOWANCE**

MS Issue Fee
Commissioner of Patents
P.O. Box 1450
Alexandria, VA 22313-1450


Dear Sir:

Applicant agrees with the Examiner's statement of reasons for allowance in that the prior art of record fails to anticipate or render obvious the claimed invention. However, Applicant notes that the Examiner's statement fails to address all limitations of all of the allowed claims. For example, certain claim limitations were not discussed in the Examiner's reasons for allowance, including those in the dependent claims, each of which defines a unique combination of features not shown or suggested by the prior art, providing additional reasons for allowance of each claim.

Applicant submits that the scope of the claims should be interpreted based on the actual language of the allowed claims, and no further limitation of the claims should be inferred from the Examiner's Statement of Reasons For Allowance.

Dated: October 23, 2009

Respectfully submitted,

By 
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